

C1 28. (Twice Amended) A sputtering target comprising tantalum metal in the shape of a sputtering target having a) an average grain size of about 50 microns or less and b) a texture in which a log ratio of (111):(100) center peak intensities of greater than about -2.0, in the substantial absence of (100) textural bands, wherein said tantalum metal has a purity of at least 99.99% tantalum.

C2 32. (Twice Amended) The sputtering target of claim 28, wherein said metal has a purity of at least 99.995% tantalum.

C3 114. (Twice Amended) The tantalum metal of claim 110, wherein said log ratio is from about -1.5 to about 7.0.

C4 120. (Amended) A tantalum sputtering component comprising an average grain size of about 150 microns or less and a uniform texture of primary (111) throughout a thickness of the component, wherein said tantalum sputtering component comprises tantalum having a purity of at least 99.99% tantalum.

C5 123. (Amended) The tantalum sputtering component of claim 122, further having 50 ppm or less O<sub>2</sub>, 25 ppm or less N<sub>2</sub>, or 25 ppm or less carbon, or combinations thereof.

C6 125. (Amended) The tantalum sputtering component of claim 124, further having 50 ppm or less O<sub>2</sub>, 25 ppm or less N<sub>2</sub>, or 25 ppm or less carbon, or combinations thereof.

C7 150. (Amended) A tantalum sputtering component comprising a uniform texture of primary (111) throughout a thickness of the component, wherein said tantalum sputtering component comprises tantalum having a purity of at least 99.99% tantalum.

C8 158. (Amended) A tantalum sputtering component comprising an average grain size of about 75 microns or less and a uniform texture of mixed (111) throughout its thickness, which is

Δ8 substantially void of (100) textural bands, wherein said tantalum sputtering component comprises tantalum having a purity of at least 99.99% tantalum.

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C9 171. (Amended) A tantalum sputtering component comprising a mixed (111) texture throughout its thickness which is substantially void of (100) textural bands, wherein said tantalum sputtering component comprises tantalum having a purity of at least 99.99% tantalum.

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Please add the following new claims.

C10 --189. A tantalum sputter component comprising an average grain size of about 75 microns or less and a uniform texture of mixed (111) throughout its thickness, wherein said tantalum sputtering component comprises tantalum sputtering component comprises tantalum having a purity of at least 99.99% tantalum.

190. The tantalum sputter component of claim 189, wherein said tantalum sputter component comprises tantalum having a purity of at least 99.995% tantalum.

191. The tantalum sputter component of claim 189, wherein said tantalum sputter component comprises tantalum having a purity of at least 99.999% tantalum.

192. The tantalum sputter component of claim 189, wherein said tantalum sputter component comprises tantalum having a purity of from 99.995% to about 99.999%.--

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